

- A New Probing System is Developed for Insulated Plasma Measurements.
- Deposition Free Measurement of Plasma Can Be Made in Floating Condition.

## 【Specifications of Probing System】

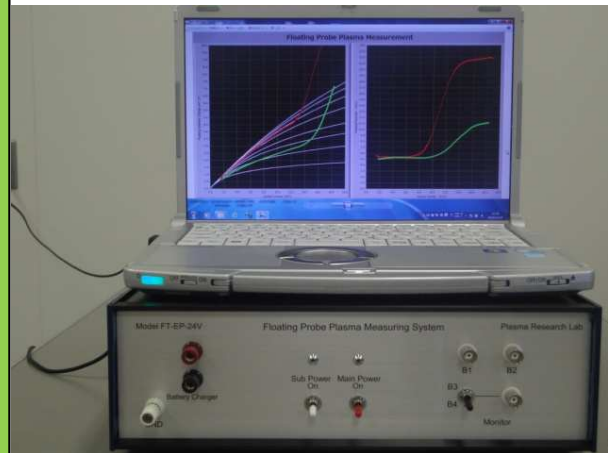
- (1) Parameters including potentials can be measured within 0.5 s in steady.
- (2) Temporal behavior can be measured in time scale of 1 milisecond.
- (3) Measurement mode can be newly designed as requested.

## 【Field Applications】

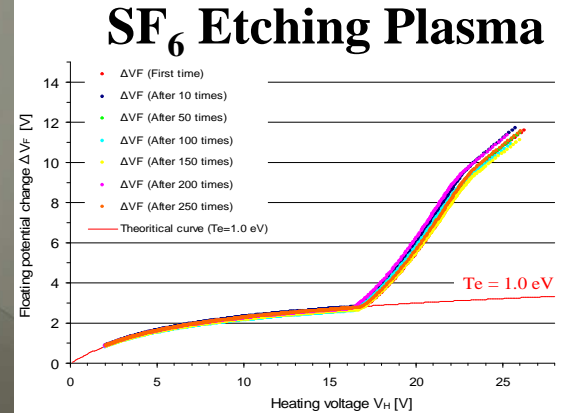
- (1) Parameter Measurements in Semiconductor Device Fabrication Plasmas
- (2) Measurable in reactive gases of SF<sub>6</sub>, O<sub>2</sub> etc.
- (3) Depo-Free Measurements in CVD and Sputter Plasma

## 【Probe Installation onto Chamber】

- (1) 6Φ Cajon Adaptor, Other Options
- (2) Probe Materials; W, Ti ,Other Options

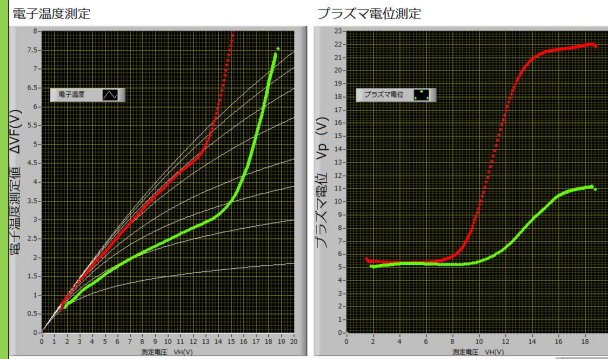


Probing System with Monitor

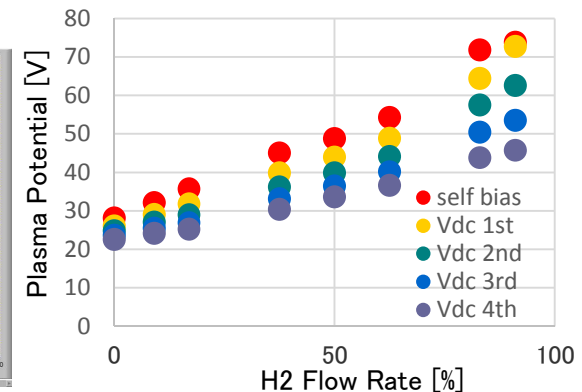


Measurements in Reactive Gas

Shindo Probing System



Left: Electron Temperature and Density Measurement  
Right: Potential Measurement



Plasma Potential Measurement in Reactive Sputter CVD

## Examples of Measured Data